

CMOS Active Pixel Sensor Development for Solar Orbiter

Development of a thinned back-illuminated CMOS Active Pixel Sensor for Extreme Ultra-Violet Spectroscopy and Imaging in Space Science

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CMOS Active Pixel Sensor Development for Solar Orbiter

- **Background**
- **4k x 3k CMOS Sensor**
- **Back-thinning**
- **New Developments**
- **Future programme**
- **Summary**

CMOS Active Pixel Sensor Development Programme

1999

- Design / modelling of pixel test structures (0.5 and 0.7 μm CMOS).

2000

- Fabrication / testing of pixel test structures.
- Established collaboration with e2v (Formerly Marconi and EEV).
 - Exchange of designs / ideas, Packaging, Testing.
 - Back-thinning \rightarrow Unique capability.
- Design of 512 x 512 pixel sensor (0.5 μm CMOS).

2001

- Fabrication of 512 x 512 pixel prototype sensors.
- e2v thinning test structures and 512 x 512 prototypes.
- Planning for Solar Orbiter (move to 0.25 μm CMOS).

2002

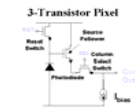
- Design and fabrication of 4k x 3k pixel sensor.
- Testing of thinned 512 x 512 pixel sensors.

2003

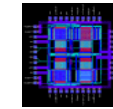
- Initial characterisation of 4k x 3k sensors.

2004/2005

- Thinning and Front-etch EUV enhancement of 4k x 3k sensors.
- Optimisation / design of high dynamic range pixels.
- Design / fabrication of new Test Structures.



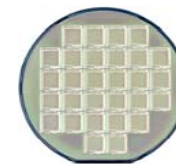
Pixel design



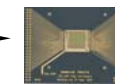
CAD layout



Packaged chip



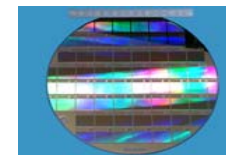
6-inch wafer



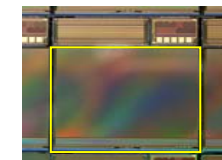
Test PCB



10Hz test image



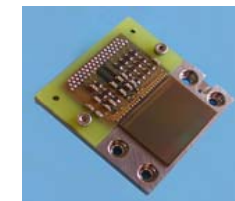
8-inch wafer



4kx3k pixel sensor die



First test image



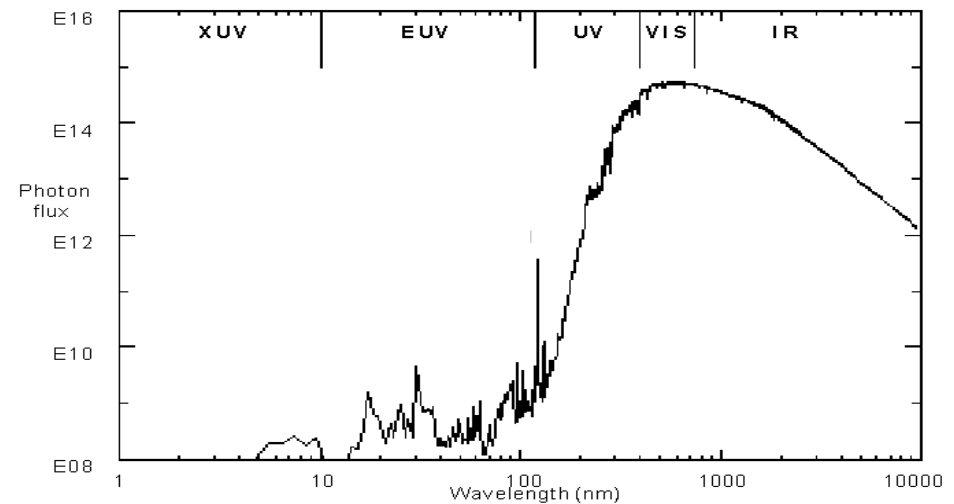
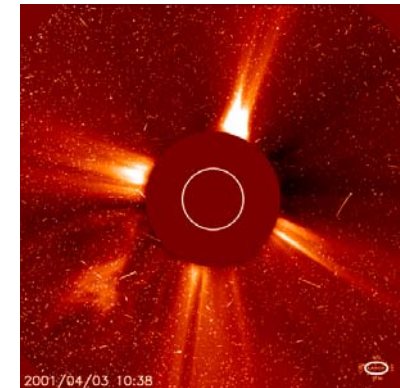
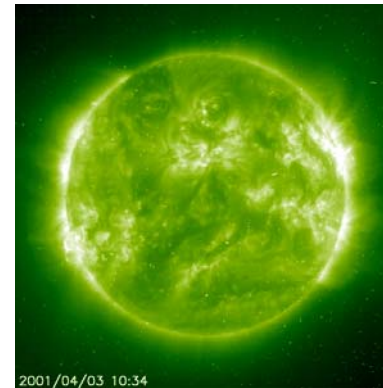
Sensor module

EUS - Spectrometer for ESA's Solar Orbiter Mission (2015?)

- To study the atmosphere and heliosphere of the Sun from close up.

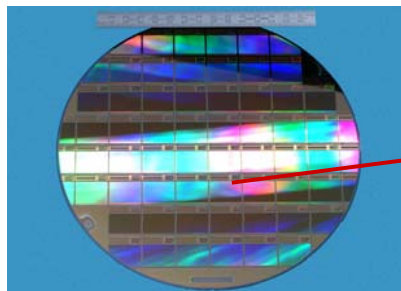
Original Requirements

- Large format sensors: 4k x 4k pixels.
- Small pixel size: 5 μm .
- Science-grade dynamic range, noise, linearity, etc.
- EUV sensitivity (17nm to 120nm).
- Radiation hard.
- Low power.

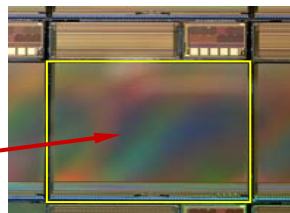


4k x 3k Pixel Sensor Development for ESA's Solar Orbiter

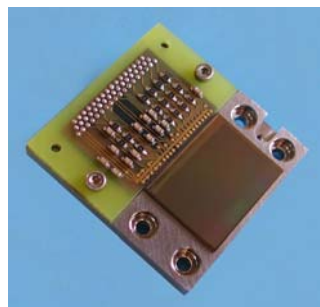
- 5 μm pixel size.
- 12 bit dynamic range.
- 4-transistor CDS pixel for low noise.
- 0.25 μm CMOS process.
- EUV sensitivity by back-thinning or front-etch.



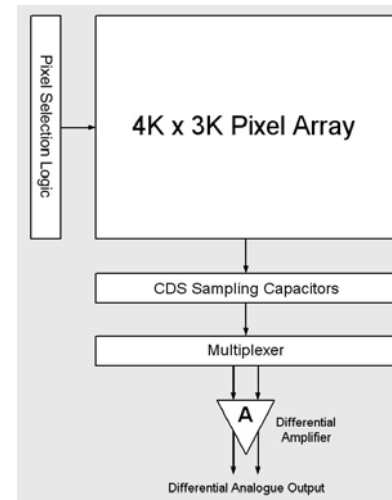
8-inch Wafer 0.25 μm CMOS



4kx3k pixel sensor die



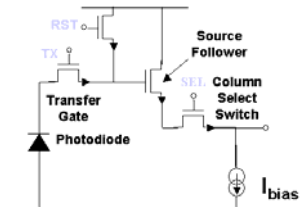
Sensor mounted on an invar block and wire-bonded to a PCB



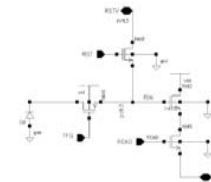
Architecture

Pixel Circuit

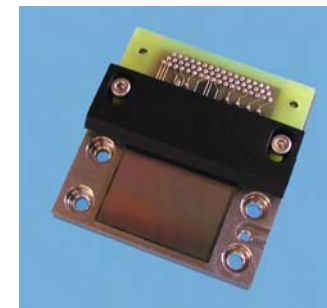
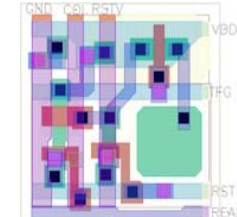
4-Transistor CDS Pixel



CAD Simulation



CAD Layout



Bond-wire protection-cover fitted

4k x 3k Pixel Sensor Development for ESA's Solar Orbiter

Progress to date . . .



Early test image 4kx3k pixels with JPEG compression for display purposes

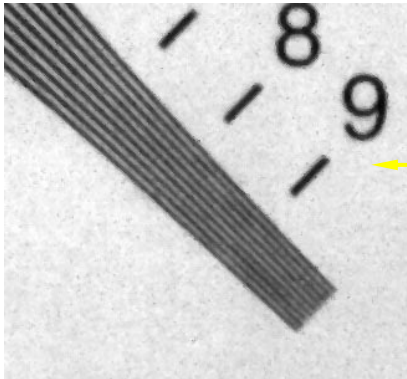
Modified Batch 1 wafers

- Early test image from modified Batch 1 wafers.
- Sufficient progress to proceed with the new Batch 2 wafers.

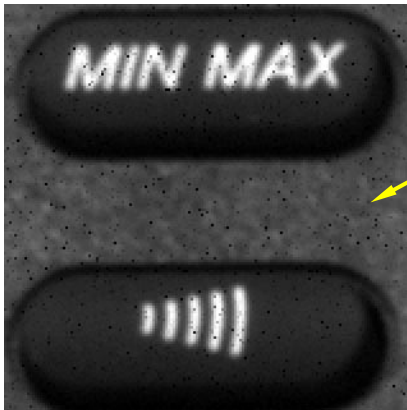
Next Steps . . .

- Characterisation of Batch 1 samples for:
 - Readout noise
 - Dynamic range
 - Linearity
 - Leakage current
 - Pixel uniformity
 - Radiation tolerance, etc.

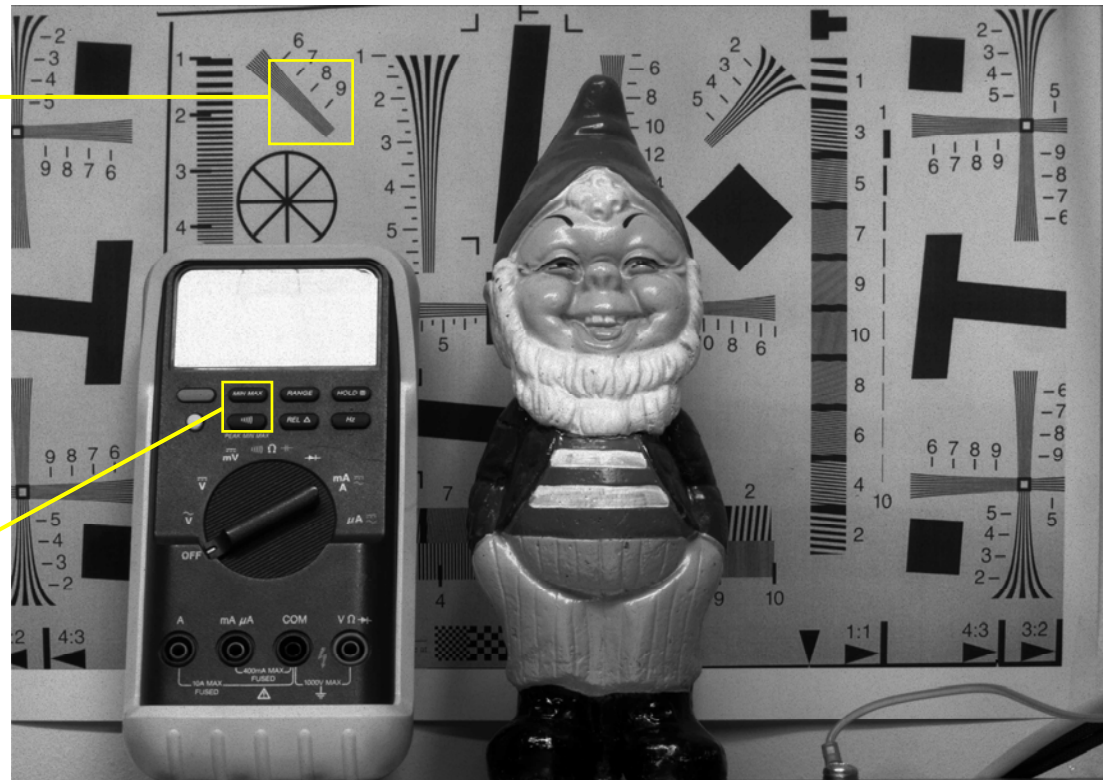
4k x 3k Pixel Sensor Development for ESA's Solar Orbiter



Raw data

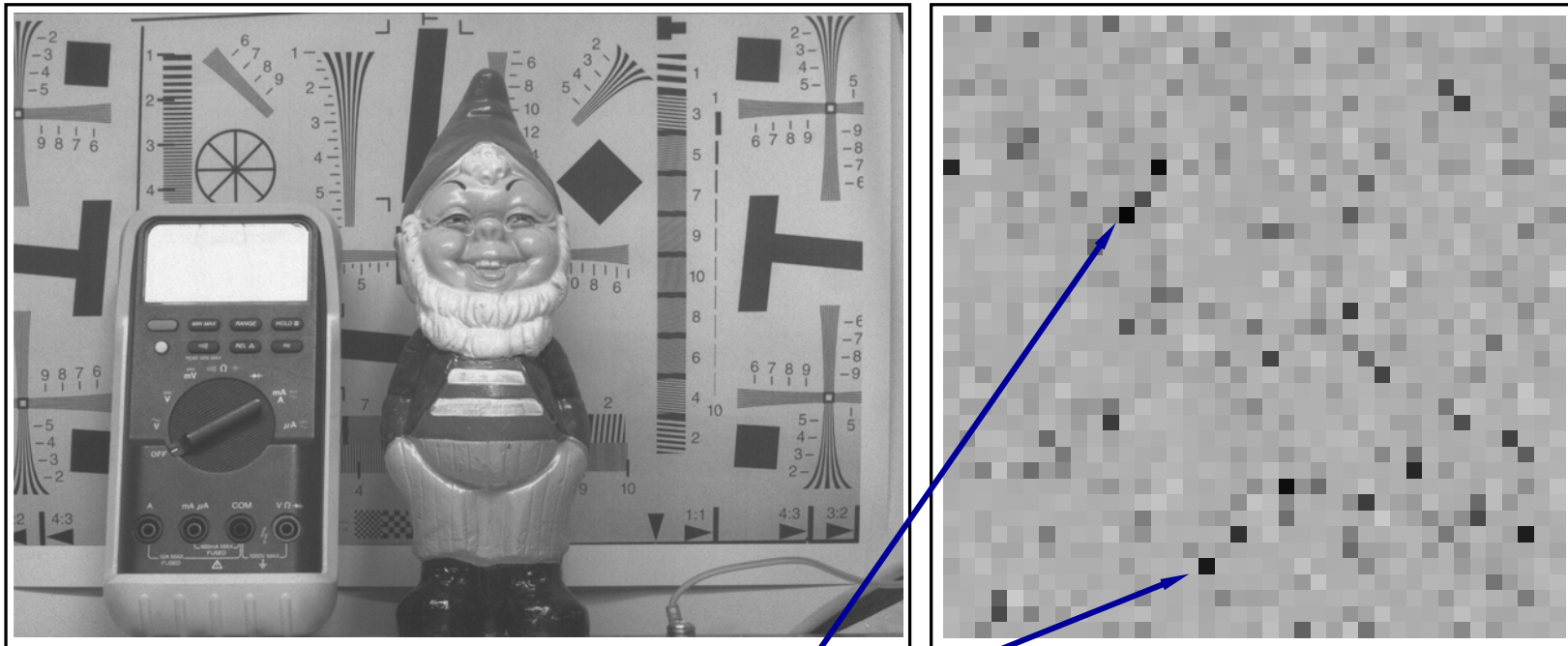


Raw data



Early test image 4kx3k pixels with JPEG compression for display purposes

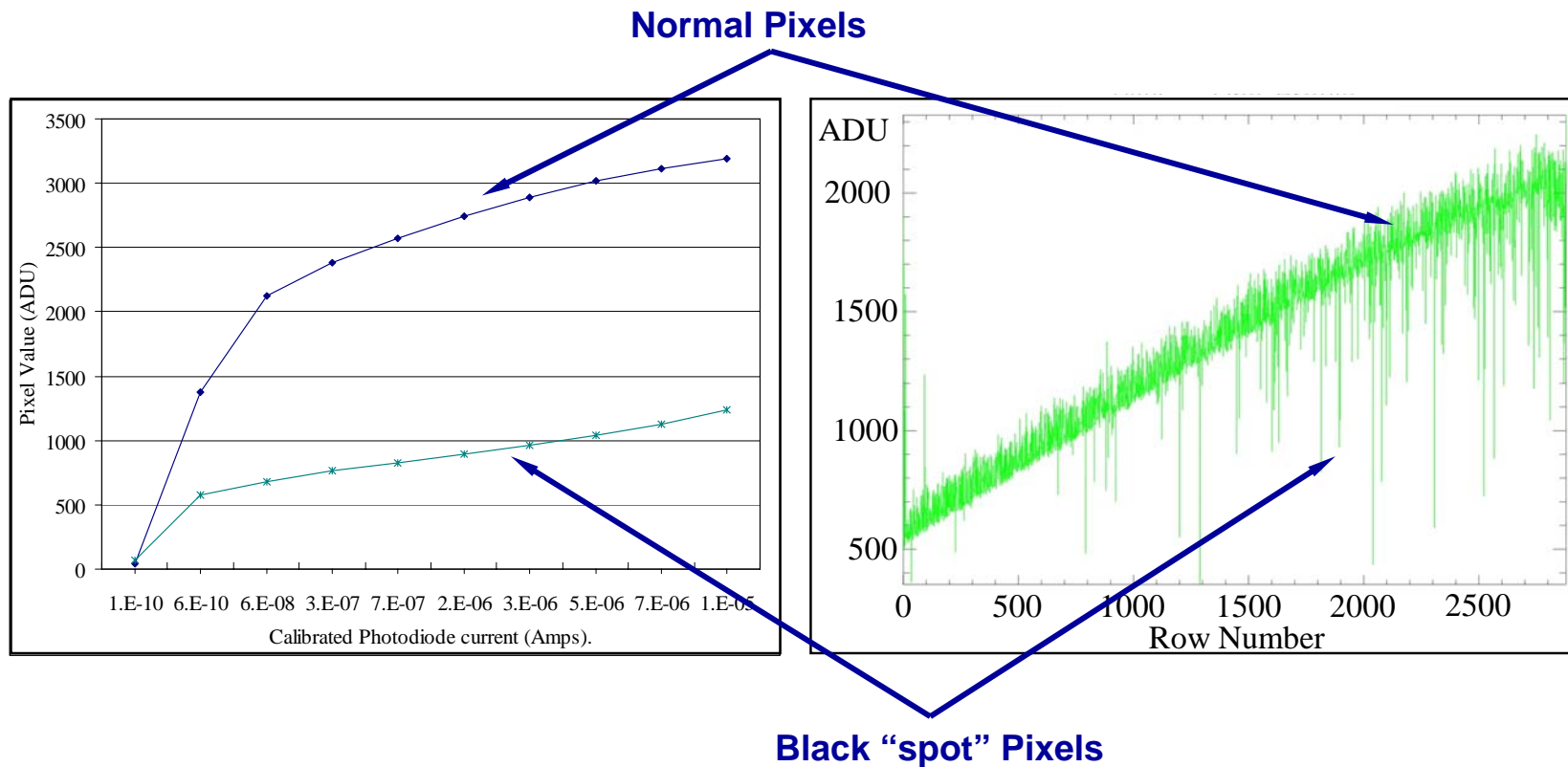
4k x 3k Pixel Sensor Development for ESA's Solar Orbiter



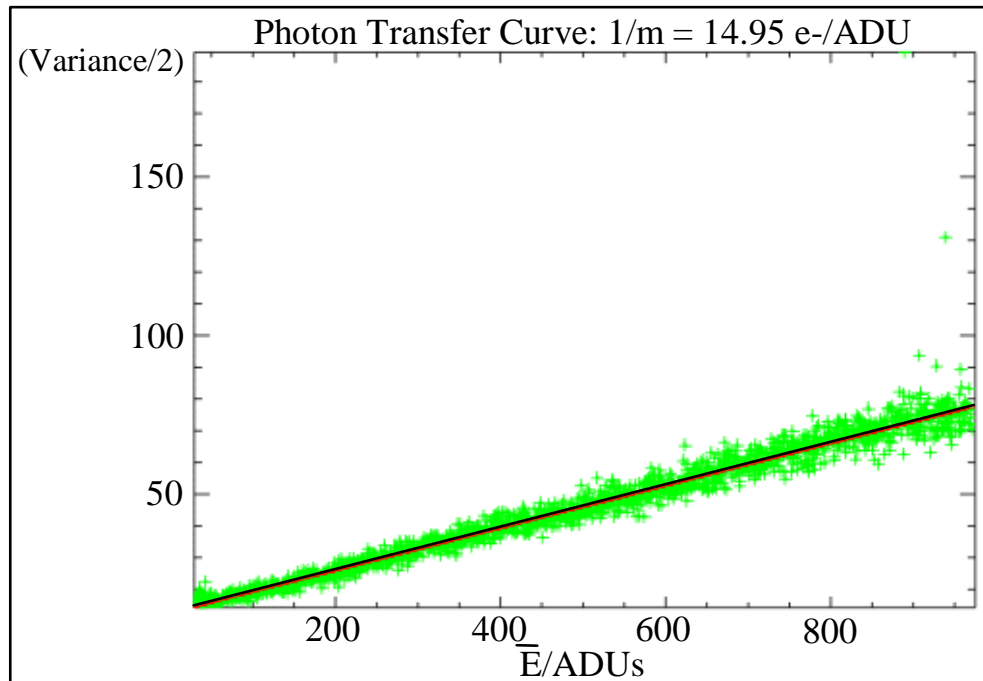
Black "spots"

4k x 3k Pixel Sensor Development for ESA's Solar Orbiter

Pixel Responsivity



4k x 3k Pixel Sensor Development for ESA's Solar Orbiter



Charge Conversion = 15 electrons/ADU

4k x 3k Pixel Sensor Development for ESA's Solar Orbiter

Dynamic Range

Useful linear dynamic range ~ 22,500 electrons **Less than expected because of need to operate the reset voltage at 2.5 V as opposed to 3.3 V.**

Noise

Expected to achieve a noise figure ~ 12 electrons rms, - assuming CDS cancellation of KTC noise.

Measured Noise: ~ 41 electrons rms.

~ 17 electrons rms. - transfer switch held off throughout.

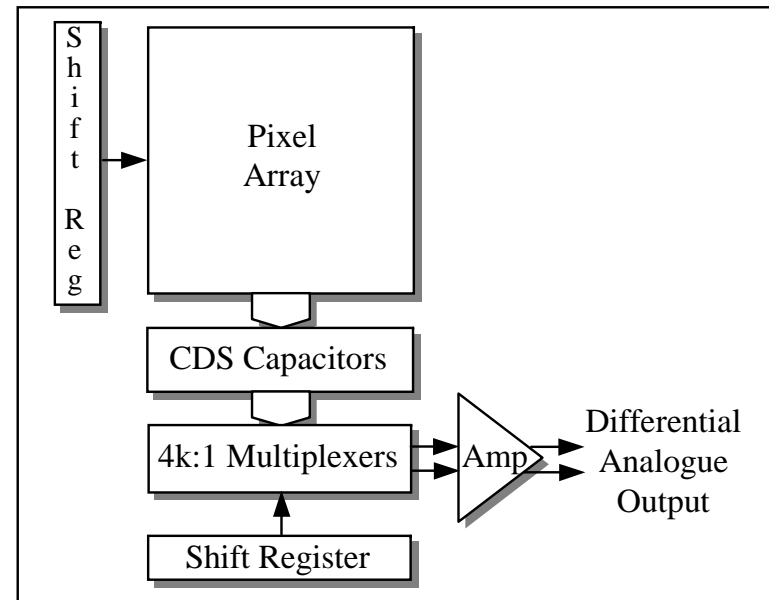
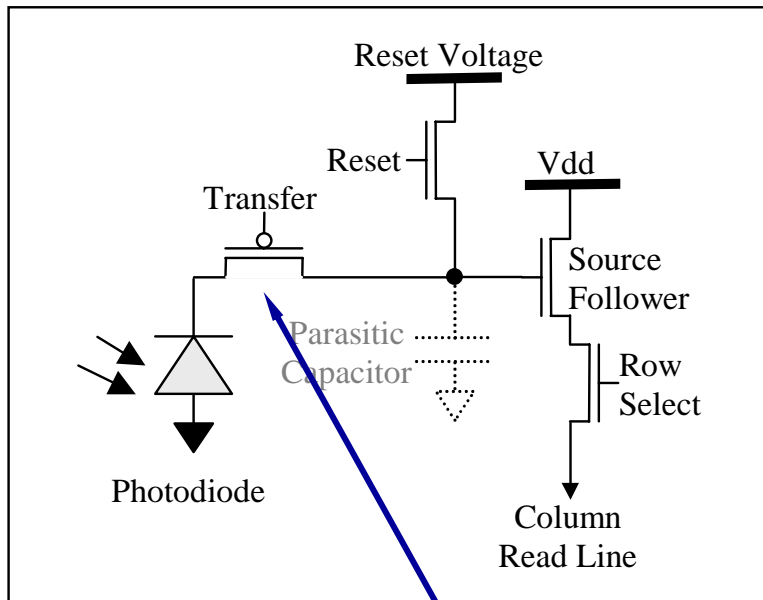
Off-Chip ADC and Readout System ~ 13 electrons rms

Just Output Amplifier operating ~ 15 electrons rms.

With the multiplexer operating ~ 16 electrons rms.

➤ It therefore appears that the excess noise arises within the actual pixel.

4k x 3k Pixel Sensor Development for ESA's Solar Orbiter

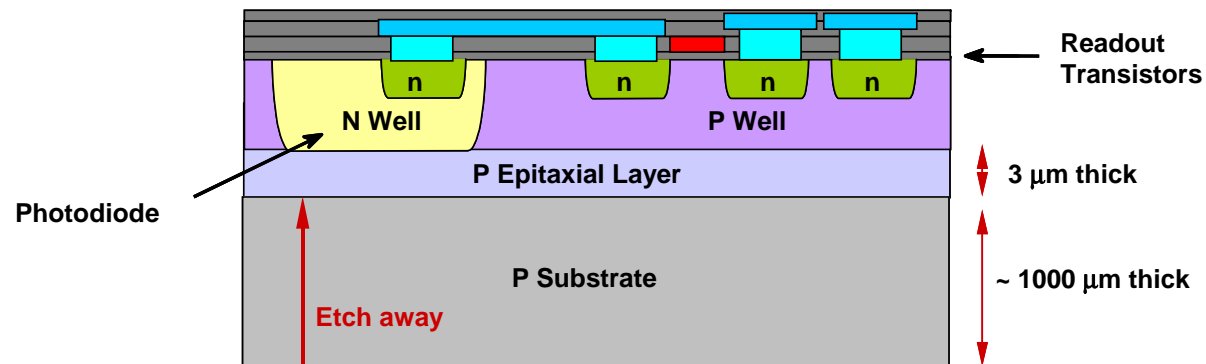


KTC noise “shared” across the total node capacitance

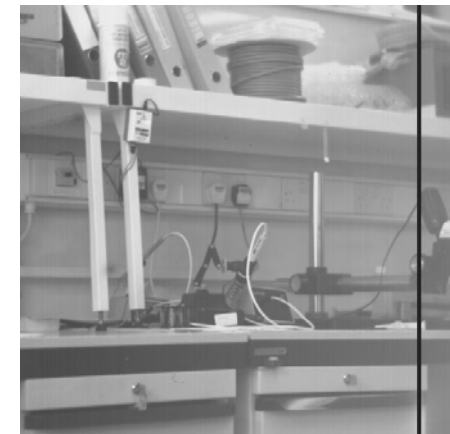
CMOS Thinning Developments with e2v technologies

Thinning of 512 x 512 pixel star tracker sensors.

- **Thinned sensors work !**
- **Limited blue response due to difficulty in thinning to the 3 μm epitaxial layer.**



Front-illuminated

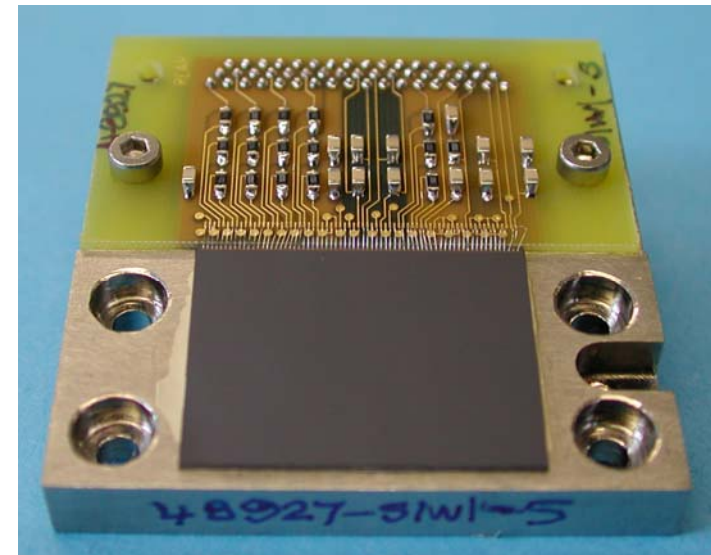
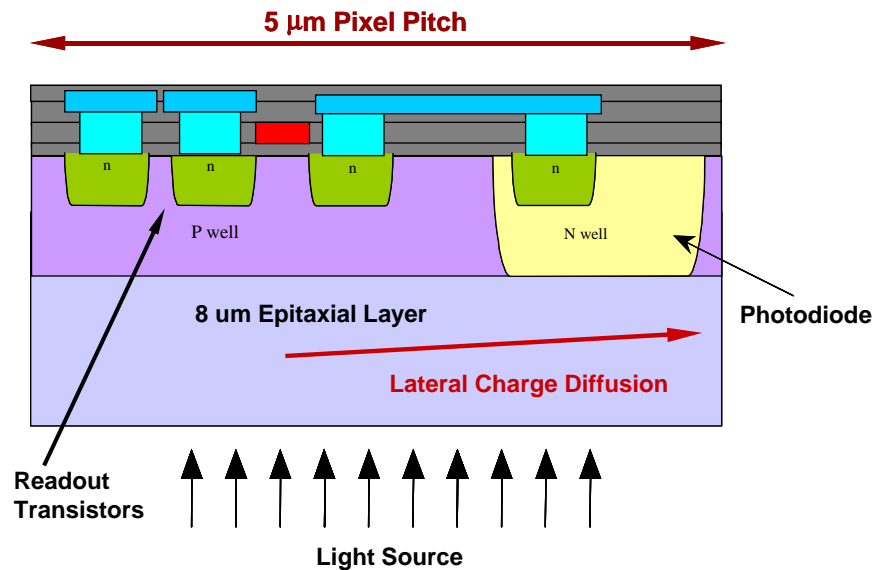


Back-illuminated

CMOS Thinning Developments with e2v technologies

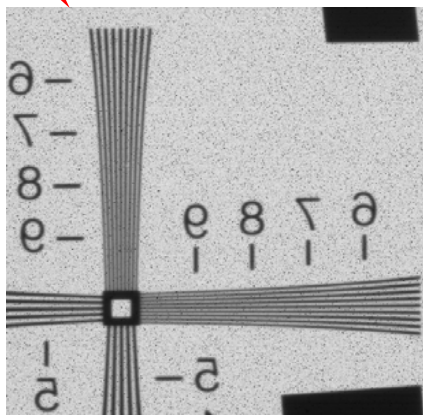
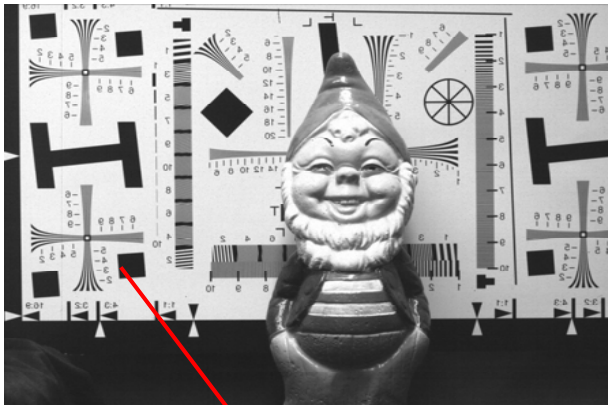
Thinning of 4kx3k pixel Wafers

- Remove bulk of wafer by diamond turning – allows better etch uniformity later on.
- Etch down into the 8 μm epitaxial layer – actually thinned to $\sim 6 \mu\text{m}$.
- Characterise EUV responsivity and MTF performance.

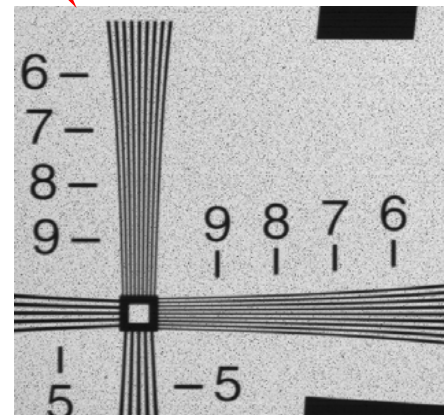


CMOS Thinning Developments with e2v technologies

Front-illuminated



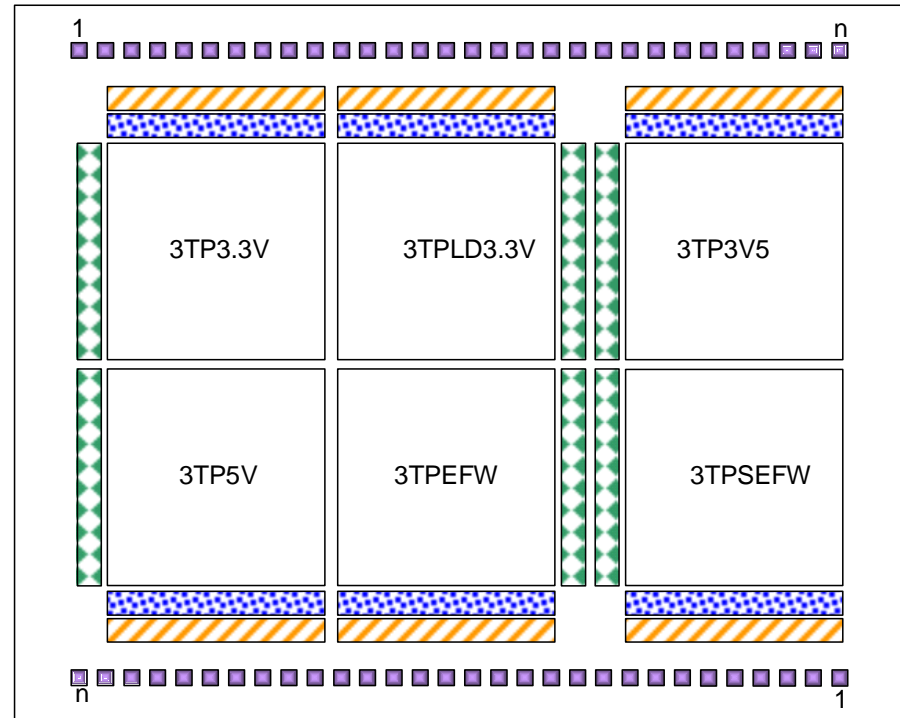
Back-illuminated







Back-illuminated image was taken through a 50nm filter at 350nm with IR-blocking filter.

New Test Structures

- 6 arrays of 512 x 512 pixels.
- 10 μm pixel size.
- Varying 3T pixel designs.
- Optimised Signal to Noise.
- Soft-reset for lower kTC.
- Maximise dynamic range.
- Thinning for EUV sensitivity.

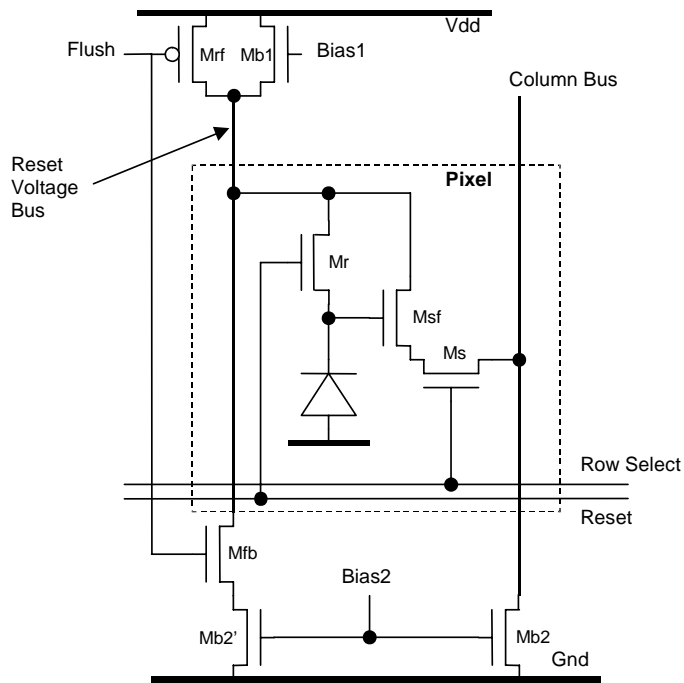


- Key**
-  Row Selection Shift Registers & Steering Logic
 -  Multiplexer Control Shift Registers
 -  Analogue Multiplexers
 -  Pads

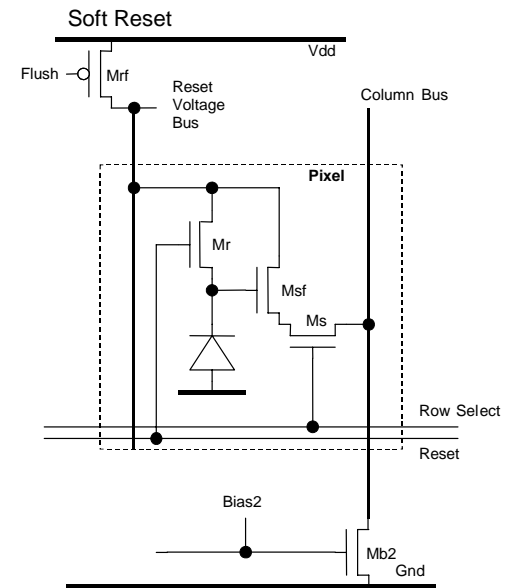
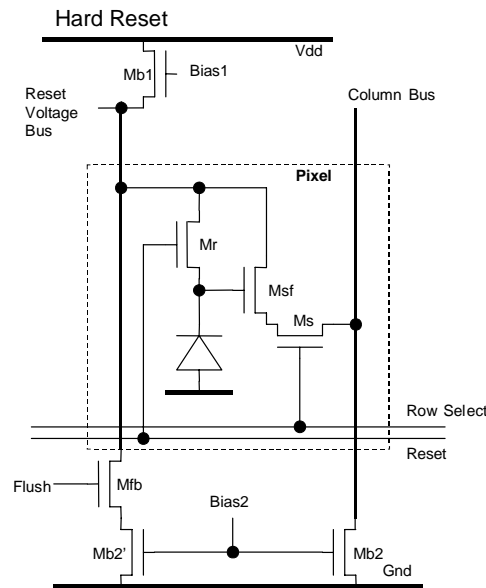
New Test Structures - Pixel Types

Pixel Name	Photodiode capacitance	Main Features
3TP3.3V	5 fF	Simple 3-transistor pixel designed for minimal capacitance and thus minimum kTC noise.
3TPLD3.3V	10 fF	Same as 3TP3.3V but optimized with larger capacitance for greater well capacity.
3TP3V5	5 fF	3.3 V and 5 V mixed voltage version of 3TP3.3V
3TP5V	5 fF	All 5 V version of 3TP3.3V.
3TPEFW	20 fF	Enhanced full-well version of 3TP3.3V with an added capacitor to maximize well capacity.
3TPSEFW	7 - 24 fF	Switchable version of 3TPEFW to allow selectable photodiode capacitance and hence well capacity.

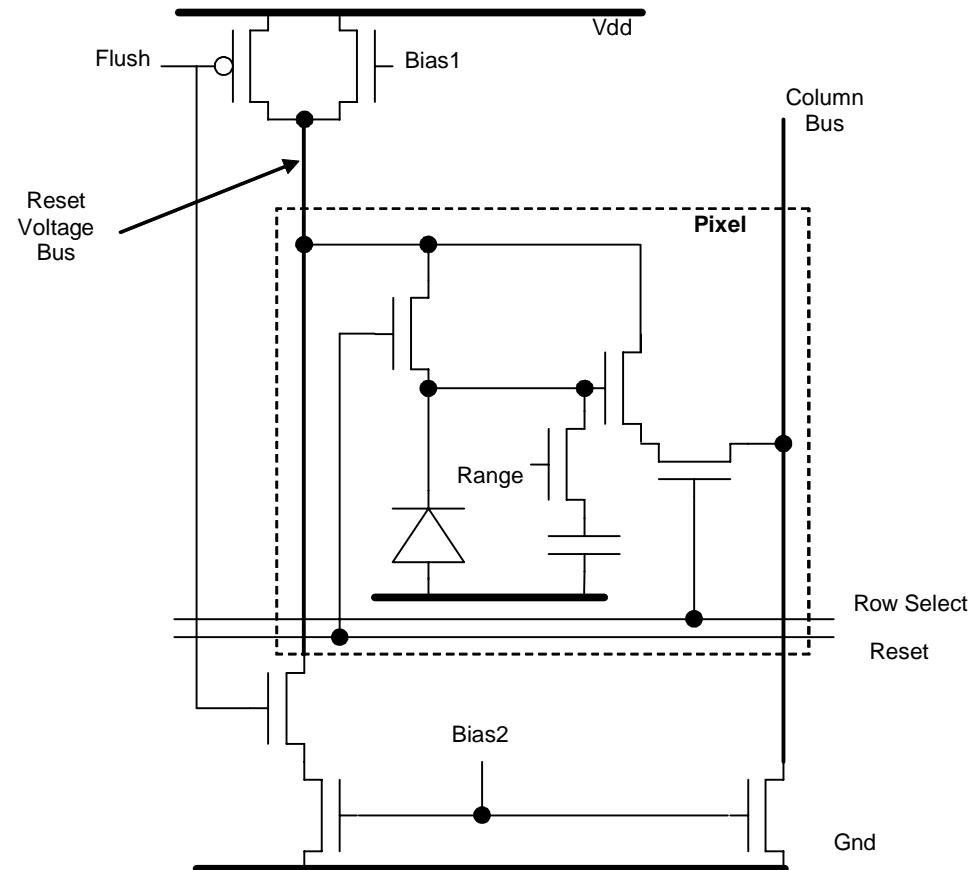
New Test Structures - Soft Reset Operation



From:
Pain, B., Yang, G. Cunningham, T.J., Wrigley, C. and Hancock, H.
An enhanced-performance CMOS imager with a flushed-reset photodiode pixel.
IEEE Transactions on Electron Devices, Vol. 50, No. 1, (2003), 48-56.

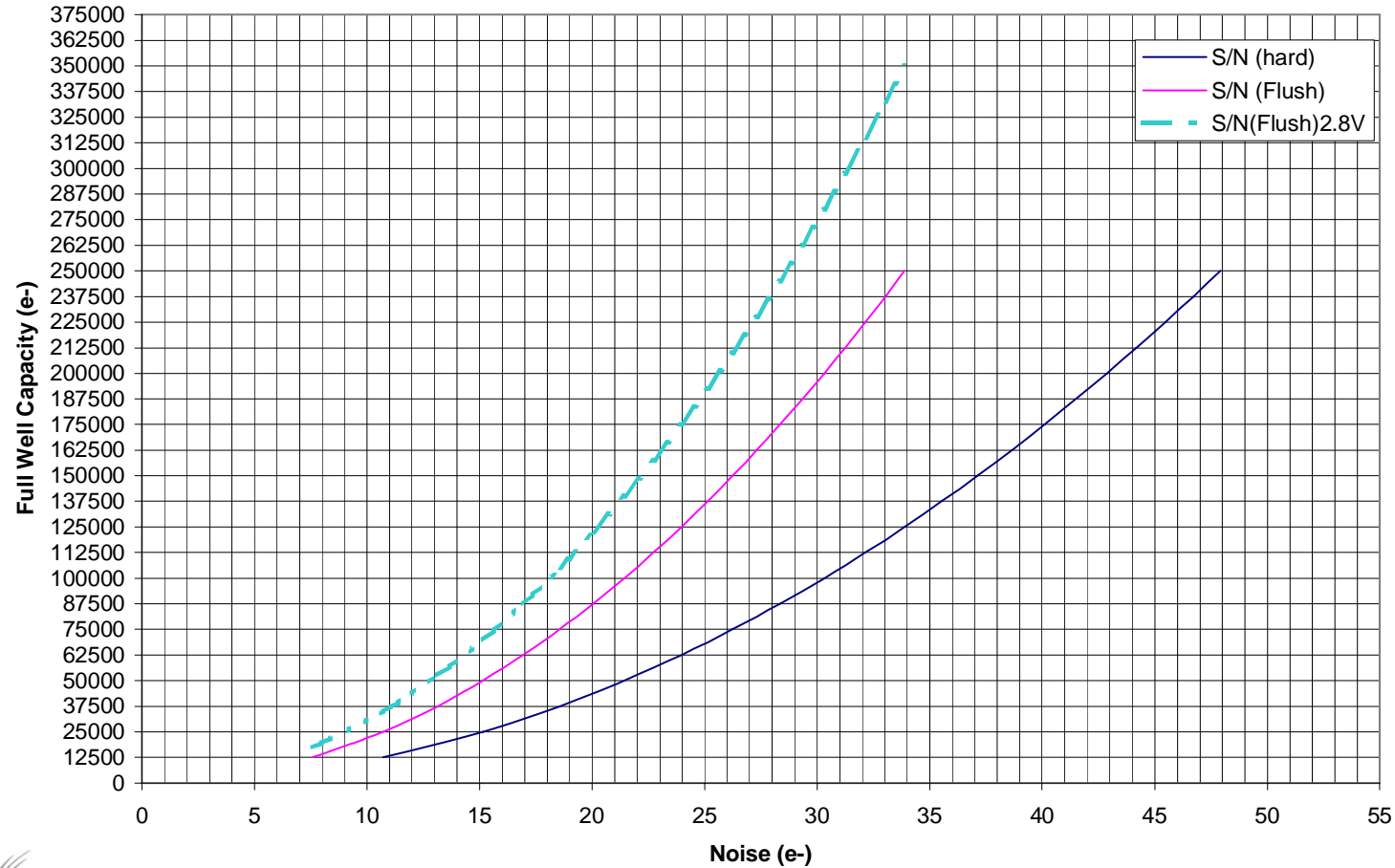


New Test Structures - Switched Capacitance Pixel



New Test Structures – Full Well vs Noise

Full well vs Noise (e-) for variation in Cdet (-60°)



Future Programme

- **Further evaluation of more back-thinned 3Kx4K for EUV sensitivity & MTF.**
 - e2v technologies are optimising the thinning process.

- **Evaluate test structures for Solar Orbiter pixels**
 - Confirm improved noise & dynamic range.
 - Determine optimal pixel for the Solar Orbiter application.
 - Radiation testing - total dose and single-event latch-up.

- **Design/build/test full-sized prototype of a Solar Orbiter detector.**

Summary

- **Demonstrated a working large format 4k x 3k pixel CMOS sensor.**
- **Further work needed to obtain necessary performance.**
- **Demonstrated the feasibility of back-thinning CMOS image sensors.**
- **Demonstrated a working back-thinned large format CMOS sensor.**